

ST-P016

## Does N<sub>2</sub>O react over oxygen vacancy on TiO<sub>2</sub>(110)?

김보성<sup>1</sup>, 김유권<sup>1</sup>, Z. Li<sup>2</sup>, Z. Dohnalek<sup>2</sup>, B.D. Kay<sup>2</sup>

<sup>1</sup>Department of Chemistry, Ajou University, <sup>2</sup>Pacific Northwest National Laboratory

Molecular N<sub>2</sub>O has been known to react over oxygen vacancy on a reduced rutile TiO<sub>2</sub>(110)-1×1 surface to desorb as molecular N<sub>2</sub> leaving oxygen atom behind. In the present study, we investigated the reaction of N<sub>2</sub>O on rutile TiO<sub>2</sub>(110) using temperature-programmed desorption (TPD). Our results indicate that N<sub>2</sub>O does not react over the oxygen vacancy under a typical UHV experimental condition. On a rutile TiO<sub>2</sub>(110)-1×1 with a well-defined oxygen vacancy concentration of 5% ( $2.6 \times 10^{13}/\text{cm}^2$ ), N<sub>2</sub>O desorption features show a monolayer peak maximum at 135 K followed by a small peak maximum at 170 K. When the oxygen vacancy is blocked with H<sub>2</sub>O, the N<sub>2</sub>O peak at 170 K disappears completely, indicating that the peak is due to molecular N<sub>2</sub>O interacting with oxygen vacancy. The integrated amount of desorbed N<sub>2</sub>O plotted against the amount of adsorbed N<sub>2</sub>O however shows a straight line with no offset indicating no loss of N<sub>2</sub>O during our cycles of TPD measurements. In addition, our N<sub>2</sub>O uptake measurements at 70~100 K showed no N<sub>2</sub> (as a reaction product) desorption except contaminant N<sub>2</sub>. Also, H<sub>2</sub>O TPD taken after N<sub>2</sub>O scattering up to 350 K indicates no change in the vacancy-related H<sub>2</sub>O desorption peak at 500 K showing no change in the oxygen vacancy concentration after the interaction with N<sub>2</sub>O.

**Keywords:** TiO<sub>2</sub>(110), N<sub>2</sub>O, TPD